

Environmentally Acceptable Photoresist Processing For Integrated Circuit Manufacture By Paula M. Wetmore

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The nanostructuring of surfaces and films using

The nanostructuring of surfaces and films using interference lithography and chalcogenide more environmentally acceptable process on more environmentally

Patent us6156221 - copper etching compositions,

environmentally acceptable, has high capacity, to have a commoning bar etchant or process that would not require a photoresist application.

Ieee xplore: semiconductor manufacturing, ieee

were utilized to demonstrate the potential for a new "dry" lithographic process. Photoresist for environmentally benign environmentally acceptable.

Patent us6638875 - oxygen free plasma stripping

Oxygen free plasma stripping process and ashing is more environmentally acceptable. The inventive stripping process for removing photoresist and/or post

Patent us6846380 - substrate processing apparatus

Microscale devices such as integrated circuits processing apparatus 10 is integrated with a processing medium distribution Wetmore; Paula M

Nanoscale research letters | full text | the

more environmentally acceptable compounds as a base for photoresist process in and films using interference lithography and chalcogenide

Www.faqs.orgwww.faqs.org

Inventor's name Country City/State Last publication Number of Patent applications; Agnar Aa: NO: Rissa: 2014-02-13 / 20140042837 - THREE PHASED BALANCED OR UNBALANCED

Presidential green chemistry challenge : award

The Presidential Green Chemistry Challenge Awards Program process is a major source of environmentally harsh environmentally acceptable,

Government contracts / supercritical fluid

Government Contracts. Applications; Processing of Energetic Materials with Environmentally Acceptable Photoresist Processing for Integrated Circuit

Chemical pre-treatment and biological destruction

.FIELD OF THE INVENTIONThe invention described herein relates to the destruction of environmentally photoresist, the photolithographic process acceptable

Immersion lithography with using of

more environmentally acceptable compounds than Chalcogenide photoresists based on thermal ty is observed in this process only in arsenic

New chemistries for advanced printed circuit board

New Chemistries for Advanced Printed Circuit environmentally acceptable manner. These photoresists are also more acceptable from an

Patente us6764552 - supercritical solutions for

the waste products generated by the various integrated circuit processing Wetmore; Paula M. wafers during manufacture of integrated

Brevetto us6764552 - supercritical solutions for

and titled Supercritical Solutions for Cleaning Photoresist and Post generated by the various integrated circuit processing Wetmore; Paula M.

Inventors list aa-ac - patent application - faqs

environmentally acceptable multifunctional multiple voltage threshold timing analysis for a digital integrated circuit: 6: photoresist processing methods: 4:

Patente us6562146 - processes for cleaning and

providing a partially fabricated integrated circuit, Wetmore; Paula M Compositions and methods for drying patterned wafers during manufacture of

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A Decision Support System for Integrated Circuit Package Selection a transaction processing monitor for distributed transaction processing applications maintains

Inventors list za-zc - patent application - faqs

MOISTURE CURABLE COMPOSITIONS AND METHODS FOR THEIR MANUFACTURE

Methods of laser processing photoresist INSULATION MATERIAL FOR INTEGRATED CIRCUITS

Spie | proceeding | advanced silicon etching using

non-corrosive environmentally acceptable silicon etching using high-density plasmas", Proc. SPIE 2639, Micromachining and Microfabrication Process

Patent us20040154641 - substrate processing -

it is becoming increasingly expensive to dispose of spent chemistries in an environmentally acceptable This patent describes use of a photoresist, and the

Brevetto wo1995024674a1 - stable, ionomeric

STABLE, IONOMERIC PHOTORESIST EMULSION AND PROCESS OF PREPARATION AND USE THEREOF. Aqueous emulsions, while more environmentally acceptable,

Www.chemeddl.org

Quantitative Analysis of Nail Polish Remover Using Nuclear Magnetic Resonance Spectroscopy Revisited Markus M. Hoffmann, Joshua T. Caccamis, Mark P. Heitz, and Kenneth

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Enviromentally acceptable photoresist processing

Enviromentally Acceptable Photoresist Processing for Integrated Circuit Manufacture. Ms. Paula Wetmore. SBIR Phase I: Plasma Deposited, Environmentally

Plating in the electronics industry - springer

Society s 9th Symposium on Plating in the Electronics Industry held under environmentally acceptable Film Photoresist Characteristics for

Brevetto ep0493923a1 - diazo sensitizers of

This solubility is preserved in the positive photoresist process in which the exposed, environmentally acceptable developer Citazioni di brevetti. Brevetto

Patent us6764552 - supercritical solutions for

and titled Supercritical Solutions for Cleaning Photoresist and Post generated by the various integrated circuit processing Wetmore; Paula M.

Patent us5268260 - photoresist develop and strip

cationically cured resists and solder masks and Vacrel photoresists. environmentally acceptable, Adhesion promotion in photoresist lamination and processing:

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Patent wo1987005314a1 - photoresist stripper

A composition, adapted to strip photoresists from substrates after the protective function of the photoresist has been completed, comprises a mixture of (a)

Advances in resist technology and processing xv |

Proceedings of SPIE Volume 3333 Advances in Paula M. Gallagher-Wetmore Novel negative photoresist based on polar alicyclic polymers for ArF

Presidential green chemistry challenge awards

that removes photoresist this new technology is more environmentally benign than the process converting wastes to more environmentally acceptable

Environmentally acceptable photoresist processing

Title: Environmentally acceptable photoresist processing for integrated circuit manufacture: Authors: Wetmore, Paula M. Affiliation: AA(Phasex Corp., Lawrence, MA.)

Patente us4201579 - method for removing

A method for removing photoresist from to provide an environmentally acceptable photoresist removal process of a photoresist stripping process:

Patent us7064070 - removal of cmp and post-cmp

requirements for every step in the manufacture of integrated circuits, and reduce particulate contamination to acceptable Wetmore; Paula M

Environmental considerations for applying

Environmental Considerations for Applying Photostructurable Liquid a technique for processing photoresist has to for an environmentally acceptable

Patent us6281135 - oxygen free plasma stripping

and ashing is more environmentally acceptable. The inventive stripping process for removing photoresist and/or post etch residues comprises generating an

United states patent [19] [11] patent number:

427531 ments and Process Studies Online , applying a photoresist to a Wafer s surface in a particular ing and Which are environmentally acceptable.

Textbook- integrated guide to educational

and printed from software supplied with the converter to afford chromatograms of acceptable An Environmentally Significant integrated circuit,

Program - symposium k: micro- and nanoscale

Program - Symposium K: Micro- and Nanoscale Processing of Materials for Biomedical Devices The integrated all-in-one system, photoresist or wax.

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